

# AQUARIUS™

A200-sa

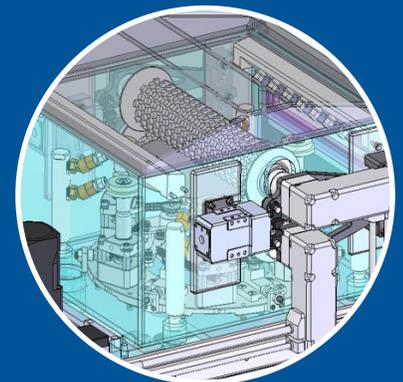
## POST CMP WAFER CLEANER



Your source for leading-edge surface processing solutions

## KEY COMPETITIVE ADVANTAGES

- Can be configured to run two different wafer sizes simultaneously
- Fully independent wafer and brush rotation control
- Top or bottom brush can rotate in either direction at any speed
- Brush compression can be controlled by 3 different metrics: position, torque, and force
- Controlled clamping force for fragile wafers in both spin and brush boxes.
- Two chemicals can run diluted or concentrated with optional on-board dilution capabilities.
- Integrated wafer flipping, nozzle megasonics, and flat finder/OCR (optional)



Aquarius Brush Box

The new and innovative Axus Technology Aquarius™ Wafer Cleaner provides improvements in all aspects of 100mm, 150mm, and 200mm wafer cleaning, including defectivity and throughput.

Features includes:

- Four brush boxes with full recipe control of all critical process variables
- Two spin-rinse-dry stations
- Two wet cassette stations in and two dry stations out
- High speed wafer handling robot with dual end effectors
- All operations can be done manually from the graphical user interface
- Three different modes of control for brush/wafer contact: position, brush torque, and contact force

Dimensions: 70"W x 56"D x 98"H

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